

SPIN RINSE DRYER µSRD



The MOT µSRD is an advanced Spin Rinse Dryer system developed by M-O-T GmbH. The µSRD is a wet process tool designed for cleaning and drying wafers for all batch applications. The standalone MOT µSRD is specially designed for easy operation and maintenance. A single cassette of wafers is placed in a stainless steel rotor. The complete buildup of the system is made of plastics (PP white) and guarantees therefore a maximal resistance against chemical attacks either of acids or bases.



SPIN RINSE DRYER µSRD Data sheet

Wafer Sizes:up to 300 mmApplications:Rinse and Drying of Wafer Baskets

Features

- Process of Wafer Baskets (25 wafers)
- High- or Low-Profile Cassettes
- Easy programming of rinse, dry and purge steps
- Balanced rotor with cassettes
- Electro polished Chamber and Rotor
- Easy exchange of Rotor

Options

- Chamber Ionization
- DI-Reclaim
- DI Heating System
- Tool less exchangeable insert made of plastic
- For running different wafer sizes
- Resistivity Monitoring
- Stainless Steel Version
- Fire suppression System for solvents

General OPTIONS

- Automatic Handling (Robot integration)
- Hot DI-Water
- Execution as fume hood
- Etching and Wetting Cells
- FM 4910 proofed material

BUILD-UP

- Material: PP white, Stainless Steel
- Door material: PVC transparent

OPERATING ELEMENTS

- All process operating elements are integrated into the front panel
- Easy Recipe Driven operation



For further questions or demands, please feel free to contact us under www.mot-semicon.com or contact@m-o-t.info M-O-T, Mikro- und Oberflächentechnik GmbH, Krughütter Straße 93, D-66128 Saarbrücken, Germany © 2002-2022 by M-O-T, All rights reserved

